

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

	00/040 700
Application Serial No	09/212,726
Filing Date De	cember 15, 1998
Inventor Klaus F	
Assignee Micron	Technology, Inc.
Group Art Unit	2813
Examiner	Erik J. Kielin
Attorney's Docket No	MI22-1098
Title: Semiconductor Processing Methods of Chemical Vapor Dep	positing SiO ₂ on
a Substrate	

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

The Examiner's attention is directed to the reference which is listed on the attached Form PTO-1449, a copy of the abstract of which is attached. No admission is made regarding whether the submitted reference is prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated: September 1

Jennifer J. Tay

Taylor, Ph.D

Reg. No. 48,

09/20/2005 EAYALEW1 00000015 09212726

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Sheet 1 of 1 SERIAL NO. Form PTO-1449 U.S. DEPARTMENT OF COMMERCE ATTY. DOCKET 09/212,726 PATENT AND TRADEMARK OFFICE NO. MI22-1098 LIST OF ART CITED BY APPLICANT **APPLICANT** (Use several sheets if necessary) Klauf Florian Schuegraf FILING DATE **GROUP** December 15, 1998 2813 **U.S. PATENT DOCUMENTS** *Examine Document Date Name Class Sub-Filing Date Number class lf Initial Appropriate AA 4,767,429 08-1988 Fleming et al. AB 5,593,741 01-1997 Ikeda AC ΑD AΕ FOREIGN PATENT DOCUMENTS Document -Date Country Class Sub-Translation Number class Yes Nο AL JP03125930 04-1992 Japan JP08130245 AM 05-1996 Japan ΑN AO AΡ OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) AQ AR AS **EXAMINER** DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.